

1 The opinion in support of the decision being entered today
2 is *not* binding precedent of the Board.

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4
5 UNITED STATES PATENT AND TRADEMARK OFFICE
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7
8 BEFORE THE BOARD OF PATENT APPEALS
9 AND INTERFERENCES
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11
12 *Ex parte* CYRUS E. TABERY, ERIC N. PATON, BIN YU,
13 QI XIANG, and ROBERT B. OGLE
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16 Appeal 2007-0661
17 Application 10/021,782¹
18 Technology Center 2800
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21 Decided: August 14, 2007
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25 Before KENNETH W. HAIRSTON, ALLEN R. MACDONALD, and
26 JAY P. LUCAS, *Administrative Patent Judges*.

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28 MACDONALD, *Administrative Patent Judge*.

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30 DECISION ON APPEAL
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¹ Filing date: December 18, 2001. The real party in interest is Advanced Micro Devices, Inc.

STATEMENT OF THE CASE

Appellants appeal under 35 U.S.C. § 134 from a Final Rejection of claims 1 and 11 entered October 7, 2004². We have jurisdiction under 35 U.S.C. § 6(b).

Appellants invented a method of manufacturing a semiconductor device that reduces the total amount of fluence required to activate the source/drain regions and increases the efficiency of the laser annealing process (Specification 3:9-12).

Claims 1, 5-11, and 13 are pending. This appeal concerns claims 1 and 11. Claims 5-10 and 13 are allowed. Claims 1 and 11 are independent claims.

As best representative of the disclosed and claimed invention, claim 1 is reproduced below:

1. A method of manufacturing a semiconductor device, comprising the steps of:
 - forming a gate electrode over a substrate;
 - introducing ions into the substrate to form source/drain regions in the substrate proximate to the gate electrode;
 - activating a portion of the source/drain regions by laser thermal annealing using a laser;
 - moving the laser and the substrate relative to one another;
- and
- activating another portion of the source/drain regions by laser thermal annealing using the laser, wherein

² An Amendment under 37 C.F.R. § 1.116 was filed on December 23, 2004, subsequent to the Final Office Action dated October 7, 2004, resulting in claims 1, 5-11, and 13 pending, with claims 5-10 and 13 allowed, and claims 1 and 11 rejected.

1 a main irradiation). Appellants contend this teaching by Yamazaki cannot
2 be reconciled with the limitations in claims 1 and 11 that recite “each pulse
3 from the laser respectively irradiates non-identical portions of the
4 source/drain regions’.” (emphasis in original) (Br. 4).

6 ISSUES

7 The issue is whether Appellants have shown that the Examiner erred
8 in rejecting representative claim 1 based on anticipation. The issue
9 specifically turns on: Whether Yamazaki expressly or inherently discloses
10 that “...*each pulse from the laser respectively irradiates non-identical*
11 *portions of the source/drain regions*”, as set forth in Appellants’ claim 1 (or
12 discloses irradiating identical portions as contended by Appellants).

14 FINDINGS OF FACT

15 The following findings of fact (FF) are supported by a preponderance
16 of the evidence.

18 *Claim Construction*

19 1. The Specification discloses that “[t]he slot or slit of a laser is the
20 surface area that is irradiated by a laser during a single pulse.”
21 (Specification, 8:1-2).

22 2. The Specification does not provide a lexicographic definition for
23 the term “portion of the source/drain regions”.

24 3. The ordinary and usual meaning of “*portion*” is, “an individual’s
25 part or share of something”. *Merriam-Webster’s Collegiate Dictionary*,
26 p. 967 (11th Edition 2005).

Yamazaki

4. Yamazaki discloses "...performing an annealing by irradiating a linear laser light onto a thin film semiconductor, and forming a plurality of semiconductor devices along the longitudinal direction of an area to which the linear laser light is irradiated." (Col. 4, ll. 29-34).

5. Yamazaki further discloses that "[a] two stage irradiation is performed... as preliminary irradiation and... as main irradiation." (Col. 7, ll. 56-59).

6. Yamazaki also discloses that "...each irradiation of the first and second laser light is conducted in such a manner that an irradiation area of one pulse is partly overlapped with a next pulse..." (Col. 10, ll. 31-34).

7. Yamazaki's title sets forth a "Method Of Producing A Semiconductor Device With Overlapped Scanned Linear Lasers." (Yamazaki, Title).

8. Yamazaki discloses that the "semiconductor film is moved relative to said pulsed laser beam continuously." (Claims 130, 140, 150).

PRINCIPLES OF LAW

"A claim is anticipated only if each and every element as set forth in the claim is found, either expressly or inherently described, in a single prior art reference." *Verdegaal Bros. v. Union Oil Co. of California*, 814 F.2d 628, 631, 2 USPQ2d 1051, 1053 (Fed. Cir. 1987). Analysis of whether a claim is patentable over the prior art under 35 U.S.C. § 102 begins with a determination of the scope of the claim. We determine the scope of the claims in patent applications not solely on the basis of the claim language, but upon giving claims their broadest reasonable construction in light of the

1 specification as it would be interpreted by one of ordinary skill in the art. *In*
2 *re Am. Acad. of Sci. Tech. Ctr.*, 367 F.3d 1359, 1364, 70 USPQ2d 1827,
3 1830 (Fed. Cir. 2004). The properly interpreted claim must then be
4 compared with the prior art.

5 The Board is required to use a different standard for construing claims
6 than that used by district courts. We have held that it is error for the Board
7 to “appl[y] the mode of claim interpretation that is used by courts in
8 litigation, when interpreting the claims of issued patents in connection with
9 determinations of infringement and validity.” *In re Zletz*, 893 F.2d 319, 321
10 (Fed. Cir. 1989); accord *In re Morris*, 127 F.3d 1048, 1054 (Fed. Cir. 1997)
11 (“It would be inconsistent with the role assigned to the PTO in issuing a
12 patent to require it to interpret claims in the same manner as judges who,
13 post-issuance, operate under the assumption the patent is valid.”). Instead,
14 as we explained above, the PTO is obligated to give claims their broadest
15 reasonable interpretation during examination. *In re Am. Acad. of Sci. Tech.*
16 *Ctr.*, 367 F.3d at 1369, 70 USPQ2d at 1834 (Fed. Cir. 2004).

18 ANALYSIS

19 For claim 11, Appellants merely repeat the same argument made for
20 claim 1. We will therefore treat claims 1 and 11 as standing or falling with
21 claim 1. *See* 37 C.F.R. § 41.37(c)(1)(vii). *See also In re Young*, 927 F.2d
22 588, 590, 18 USPQ2d 1089, 1091 (Fed. Cir. 1991).

23
24 Issue A: Whether Yamazaki expressly or inherently discloses that
25 “...each pulse from the laser respectively irradiates non-identical
26 portions of the source/drain regions”, as set forth in Appellants’
27 claim 1.

1 The Specification discloses that “the slot or slit of a laser is the
2 surface area that is irradiated by a laser during a single pulse.” (FF 1).
3 As such, a reasonable construction of the term “portion of the source/drain
4 regions” is the surface area that is irradiated by a single pulse. (FF 2-3).

5 Appellants contend that Yamazaki teaches that an identical portion of
6 a particular source/drain region is irradiated by two or more pulses...This
7 teaching of Yamazaki cannot be reconciled with the limitations in claims 1
8 and 11 that recite “each pulse from the laser respectively irradiates non-
9 identical portions of the source/drain regions.” (Br. 4-5). We disagree.

10 While Yamazaki discloses using a two stage irradiation process
11 (FF 4-5), Appellants have not shown how such a two step irradiation process
12 equates to “an identical portion” of a particular source/drain region being
13 irradiated by two or more pulses. In an attempt to bolster this position,
14 Appellants contend that “because stripes are necessarily formed, it is readily
15 apparent that Yamazaki does not disclose continuous movement of the
16 substrate relative to the laser” (emphasis in original)(Reply Br. 2:12-13).
17 Again, we disagree.

18 For example, Yamazaki expressly discloses that the semiconductor
19 film is continuously moved relative to the pulsed laser beam. (FF 8).
20 Furthermore, Yamazaki discloses that each irradiation performed by the first
21 and second laser (i.e., two stage irradiation) is conducted in such a manner
22 that an irradiation area (i.e., a portion of the source/drain region) of one
23 pulse is partly overlapped with a next pulse (FF 6-7).

24 In other words, Yamazaki discloses a continuously moving
25 semiconductor film that receives “partly overlapped” pulses from the lasers
26 from one pulse to the next. (FF 6)

1 In addition, Appellants state that “Independent claims 1 and 11 both
2 recite that ‘each pulse from the laser respectively irradiates non-identical
3 portions of the source/drain regions.’ This feature is illustrated, for example,
4 in Fig. 3 of Appellants’ disclosure, which shows pulses 1-5 impinging on
5 non-identical portions of the substrate 100.” (emphasis in original) (Br.
6 4:1-4). As such, Appellants admit that Fig. 3 of Appellants’ disclosure
7 illustrates the claimed non-identical portions. From a review of Appellants’
8 Fig. 3, it is clear to us that such non-identical portions are also partly
9 overlapped. Thus, it is our view that Appellants’ Fig. 3 is showing non-
10 identical portions that are “partly overlapped” with each other. Therefore,
11 Yamazaki’s disclosed partly overlapped pulses read on Appellants’ non-
12 identical portions.

13 Appellants also argue that “Yamazaki clearly teaches away from the
14 claimed invention by advocating a two step irradiation” (Br. 6). We begin
15 our analysis by noting that the Court of Appeals for the Federal Circuit has
16 determined “[t]eaching away is irrelevant to anticipation.” *Seachange*
17 *International, Inc., v. C-Cor, Inc.*, 413 F.3d 1361, 1380, 75 USPQ2d 1385,
18 1398 (Fed. Cir. 2005), citing *Celeritas Tech., Ltd., v. Rockwell Int’l Corp.*,
19 150 F.3d 1354, 1361, 47 USPQ2d 1516, 1522 (Fed. Cir. 1998); *Bristol-*
20 *Myers Squibb Co. v. Ben Venue Labs., Inc.*, 246 F.3d 1368, 1378, 58
21 USPQ2d 1508, 1515 (Fed. Cir. 2001). Therefore, Appellants’ reliance on
22 Yamazaki’s two step irradiation process to show disincentive in the cited
23 reference to irradiate non-identical portions of the source/drain regions is
24 misplaced. Such arguments are therefore not persuasive.

CONCLUSIONS

We conclude that Appellants have not shown that the Examiner erred in rejecting claims 1 and 11.

Thus, on this record claims 1 and 11 are not patentable.

DECISION

In view of the foregoing discussion, we affirm the Examiner's rejection of claims 1 and 11.

No time period for taking any subsequent action in connection with this appeal may be extended under 37 C.F.R. § 1.136(a). *See* 37 C.F.R. § 1.136(a)(1)(iv) (2006).

AFFIRMED

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MCDERMOTT WILL & EMERY LLP
600 13TH STREET, N.W.
WASHINGTON DC 20005-3096